

ABSTRACT

A porous film with chemical resistance of this invention includes a porous film base covered with a chemical-resistant polymeric compound and has a multiplicity of communicating micropores having an average pore size of 0.01 to 10  $\mu\text{m}$ . The chemical-resistant polymeric compound can be, for example, any of phenolic resins, urea resins, melamine resins, benzoguanamine resins, polyimide resins, epoxy resins, benzoxazine resins, polypropylene resins, polyurethane resins, fluororesins, alkyd resins, cellulose acetate resins, phthalic resins, maleic resins, and silicone resins.